



Dual Ion Beam Sputtering Deposition (DIBSD): The diverse novel researches performed by this unique facility will be a platform to attract top-seeded researchers and experimentalists in key semiconductor opto-electronic and nanotechnology industries, research laboratories, and academic institutions across the entire globe to establish a strong collaborative research programme with IIT Indore. Research activities, boosted by the DIBSD facility, are mainly focused on growth of novel nanostructures and high-quality thin films having enormous applications in semiconductor opto-electronics, sensors, solar photovoltaics, detectors, biotechnology, microelectro-mechanical systems (MEMS), nanoelectromechanical systems (NEMS) etc.

Diverse novel research activities would have major impact on following industries:

- Automobile
- Nanotechnology
- Pharmaceutical (Nano-Bioelectronics)
- Electronics
- Chemical
- Renewable Energy

In a broad sense, the research work accomplished by this facility would be extremely beneficial to showcase our expertise in the emerging areas of current research and development. The high-tech research and developmental work performed by the DIBSD facility would usher the achievement of possible leadership of the institute in the niche area of innovative research fields in near future. With this advanced research facility and high level of expertise, we can offer our experimental services to other Schools within the Institute sector and external commercial organizations and academic institutions.